

U.S. Department of Commerce, Patent and Trademark Office

Docket No.

Serial No.

AMAT/3434/PDD/KPU1/JW

09/270,039

LIST OF RELEVANT ART CITED BY APPLICANT

Applicant

(Use several sheets if necessary)

Judy H. Huang

Filing Date

Group

March 16, 1999

Unknown

2823

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
G	AA	5,565,084	10/15/1996	Lee et al.	205	646	10/15/1996
	AB						
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	AM						

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Foreign Patent Documents

Translation

		Date	Country	Class	Subclass	Yes	No
	AN						
	AO						

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AP	
	AQ	

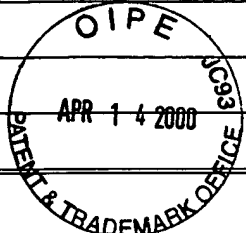
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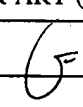
3/27/02

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U.S. Department of Commerce, Patent and Trademark Office				Doc. No.		Serial No.	
(PTO Form 1449 modified)				AMAT/3434/PDD/KPU1/JW		09/270,039	
LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT				Applicant			
(Use several sheets if necessary)				Judy H. Huang			
				Filing Date		Group	
				March 16, 1999		2813 2823	
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*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	3,510,369	05/05/70	Ernick et al.	148	187	
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	AN	0 613 178 A2	02/22/1994	EPO	H 01 L	21/90	N/A	
	AO	WO 99/33102	07/01/1998	PCT International	H 01 L	21/767	N/A	
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	AR PCT International Search Report for PCT/US99/22425 Dated February 2, 2000
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Examiner <i>Fourson</i>	Date Considered <i>3/27/02</i>
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(Use several sheets if necessary)	Judy H. Huang	
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	March 16, 1999	Unknown 2823

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G	AA	5,741,626	04/21/1998	Jain et al.	430	314	04/15/1996
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		Document Number	Date	Country	Class	Subclass	Yes	No
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G	AP	Ogawa et al., "Novel ARC Optimization Methodology for KrF Excimer Laser Lithography at Low K1 Factor", <i>Proceedings of the SPIE. Optical/Laser Microlithography V</i> , vol. 1674, 1992, pages 362-375.
G	AQ	Dijkstra et al., "Optimization of Anti-Reflection Layers for Deep UV Lithography", <i>Proceedings of SPIE Optical/Laser Microlithography, Bellingham, SPIE</i> , vol. 1927, pages 275-286.
G	AR	PCT International Search Report dated March 9, 2000, for PCT/US99/22424.
G	AS	PCT Partial International Search Report dated March 21, 2000, for PCT/US99/22317.

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